

Appl. No. 09/699,897

REMARKS

Claims 28-33 are pending in the application with claims 1-27 canceled herein as being drawn to a non-elected invention. Applicant hereby elects Group II, claims 28-33, without traverse for prosecution on the merits. Applicant requests favorable consideration in the next Office Action.

Respectfully submitted,

Dated: 30 Jan 2003

By: _____

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GROUP 1700

Application Serial No. 09/699,897
Filing Date October 27, 2000
Inventor Mathew S. Cooper
Assignee..... Micron Technology, Inc.
Group Art Unit 1753
Examiner R. McDonald
Attorney's Docket No. H0001190 (4016)
Title: Physical Vapor Deposition Components and Methods of Formation

**VERSION WITH MARKINGS TO SHOW CHANGES MADE ACCOMPANYING
RESPONSE TO JANUARY 2, 2002 OFFICE ACTION**

In the Claims

The claims have been amended as follows. Underlines indicate insertions and ~~strikeouts~~ indicate deletions.

28. (once amended) A PVD component produced by the method ~~of claim 1~~
comprising inducing a sufficient amount of stress in the component to increase
magnetic pass through flux exhibited by the component compared to pass through flux
exhibited prior to inducing the stress.

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29. (once amended) A sputter component produced by the method of claim-24 comprising:

unidirectionally first cold working a component blank to at least about an 80% reduction in cross-sectional area;

heat treating the cold worked component blank at least at about a minimum recrystallization temperature of the component blank; and

inducing a sufficient amount of stress in the heat treated component to increase magnetic pass through flux exhibited by the heat treated component compared to pass through flux exhibited prior to inducing the stress.

30. (once amended) A sputter target produced by the method of claim-26 comprising:

unidirectionally first cold rolling a target blank consisting essentially of nickel to at least about an 85% reduction in cross-sectional area;

heat treating the cold rolled target blank at a temperature between about 427 °C (800 °F) to about 482 °C (900 °F) for less than about 60 minutes; and

second cold rolling the heat treated target blank to a reduction in cross-sectional area of about 10% of the heat treated component, at least about 70% of a surface area at least within selected boundaries of a surface of the second cold rolled target blank exhibiting a (200) texture.

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